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标题: A computational study of high-frequency behavior of graphene field-effect transistors

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摘要: High Frequency potential of graphene field-effect transistors (FETs) is explored by quasi-static self-consistent ballistic and dissipative quantum transport simulations. The unity power gain frequency $f(\text{MAX})$ and the cut-off frequency $f(\text{T})$ are modeled at the ballistic limit and in the presence of inelastic phonon scattering for a gate length down to 5 nm. Our major results are (1) with a thin high-k gate insulator, the intrinsic ballistic $f(\text{T})$ is above 5 THz at a gate length of 10 nm. (2) Inelastic phonon scattering in graphene FETs lowers both $f(\text{T})$ and $f(\text{MAX})$, mostly due to decrease of the transconductance. (3) $f(\text{MAX})$ and $f(\text{T})$ are severely degraded in presence of source and drain contact resistance. (4) To achieve optimum extrinsic $f(\text{MAX})$ performance, careful choice of DC bias point and gate width is needed. (C) 2012 American Institute of Physics. [<http://dx.doi.org/10.1063/1.4712323>]

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